

WET BENCH: OXIDE ETCH + HYDROPHILIC CLEAN (RCA CLEAN)

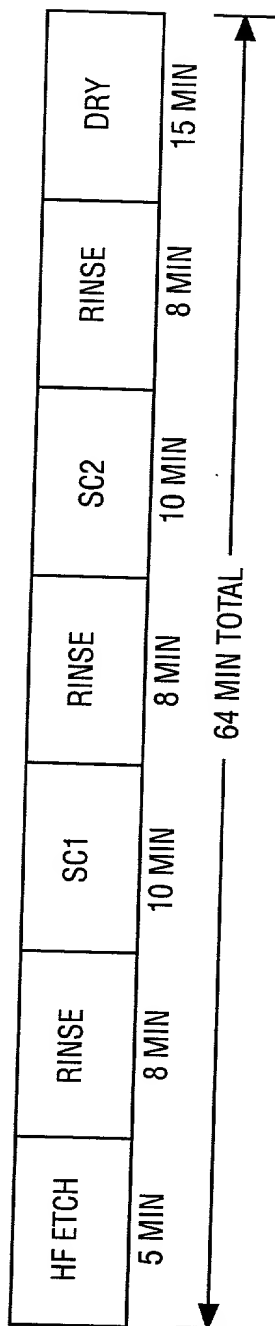


FIG. 1a

SINGLE WAFER CLEANING TOOL SINGLE STEP CLEAN
OXIDE ETCH + HYDROPHILIC CLEAN

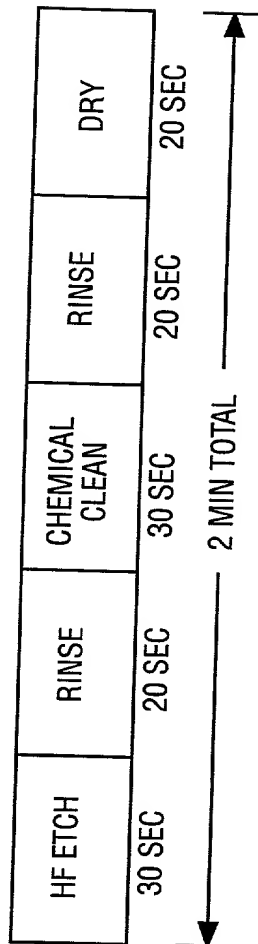


FIG. 1b

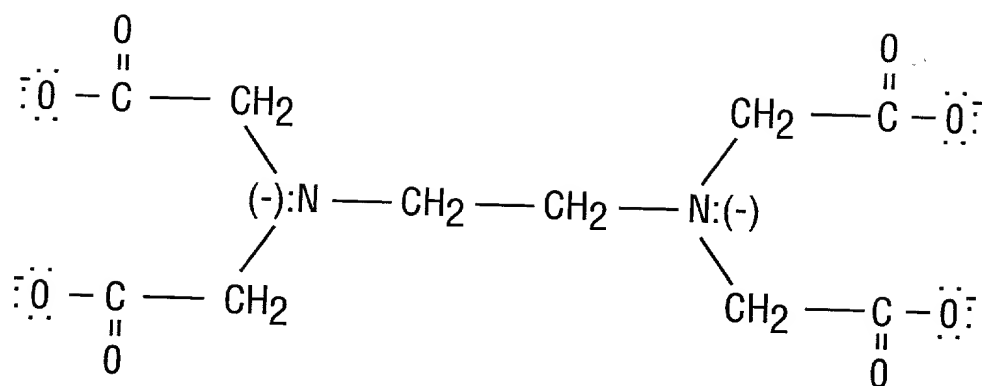


FIG. 2a

BINDS METAL IONS

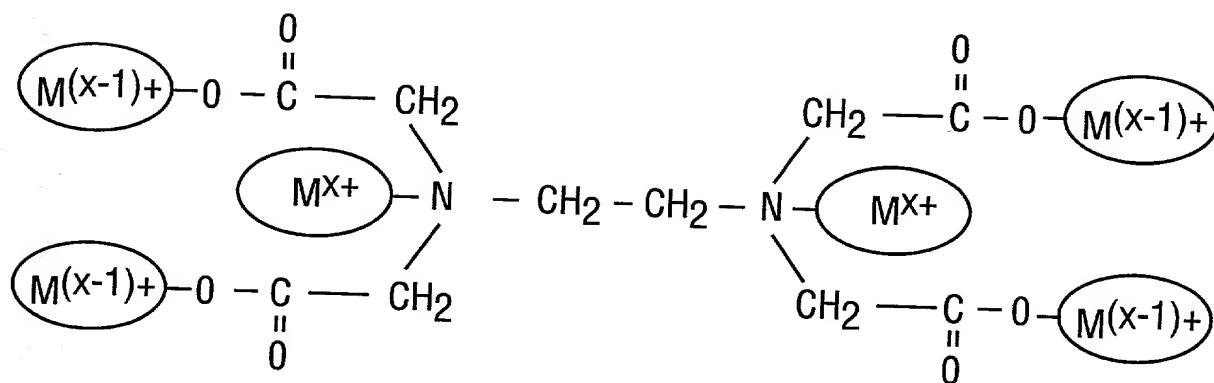
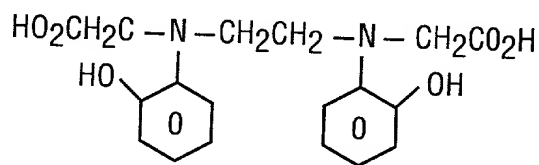
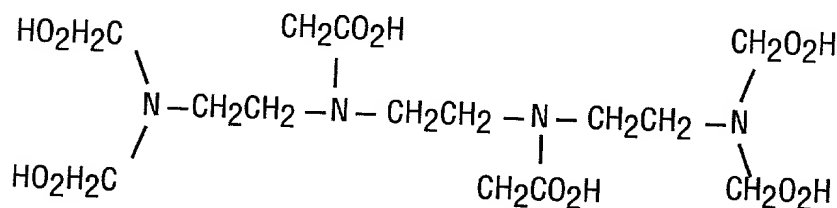


FIG. 2b



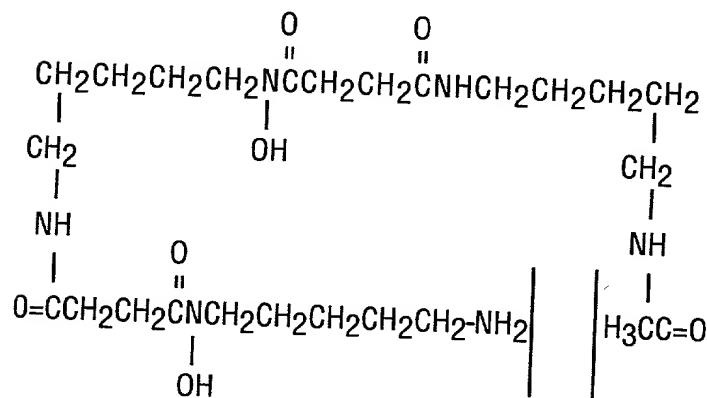
(HPED)

FIG. 3a



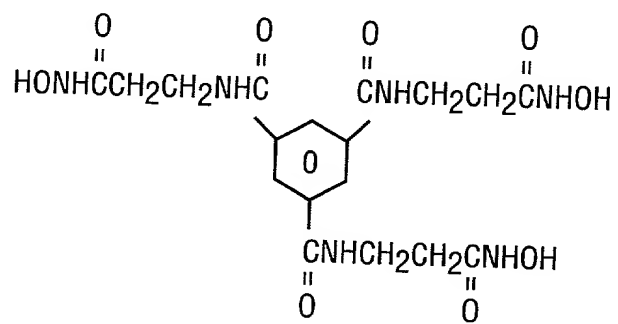
(TTHA)

FIG. 3b



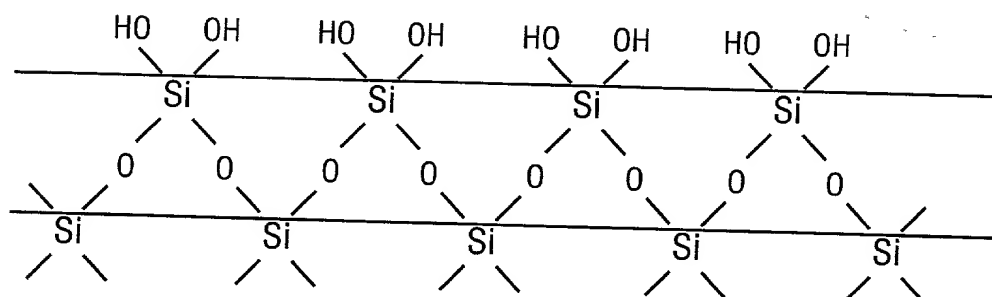
DESFERRIFERRIOXAMIN B

FIG. 3c



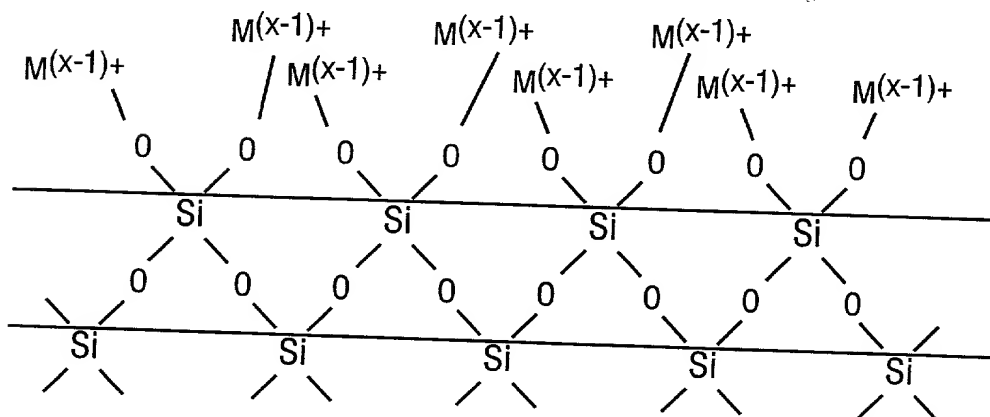
(BAMTPH)

FIG. 3d



HYDROXIDE
TERMINATED SiO_2 FILM

FIG. 4a



CHEMISORPTION

FIG. 4b

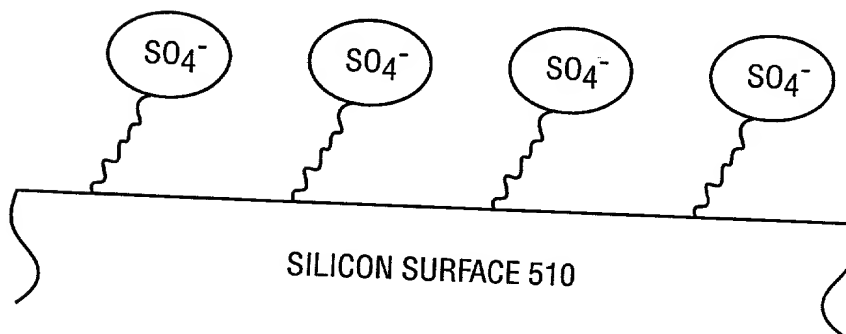
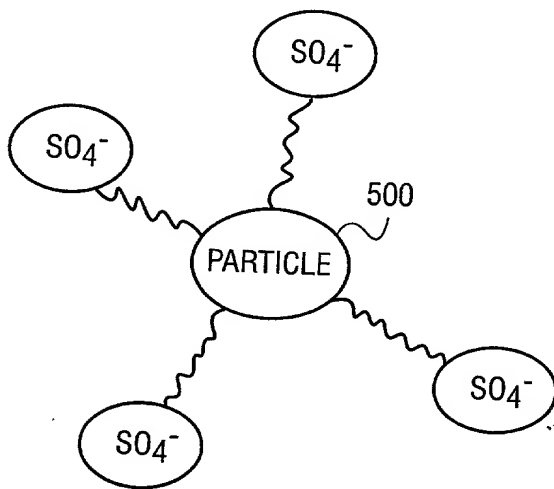


FIG. 5

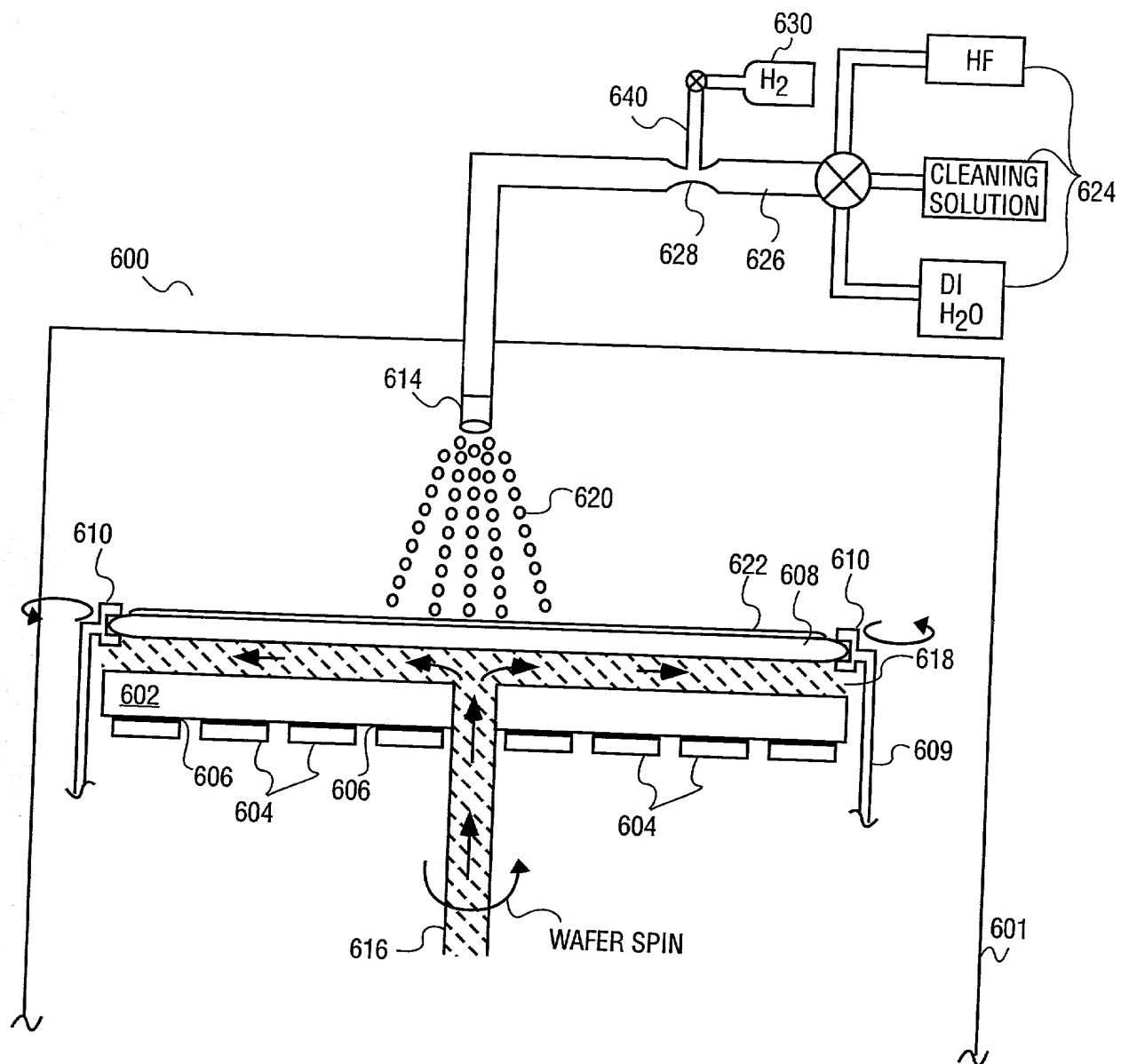


FIG. 6a

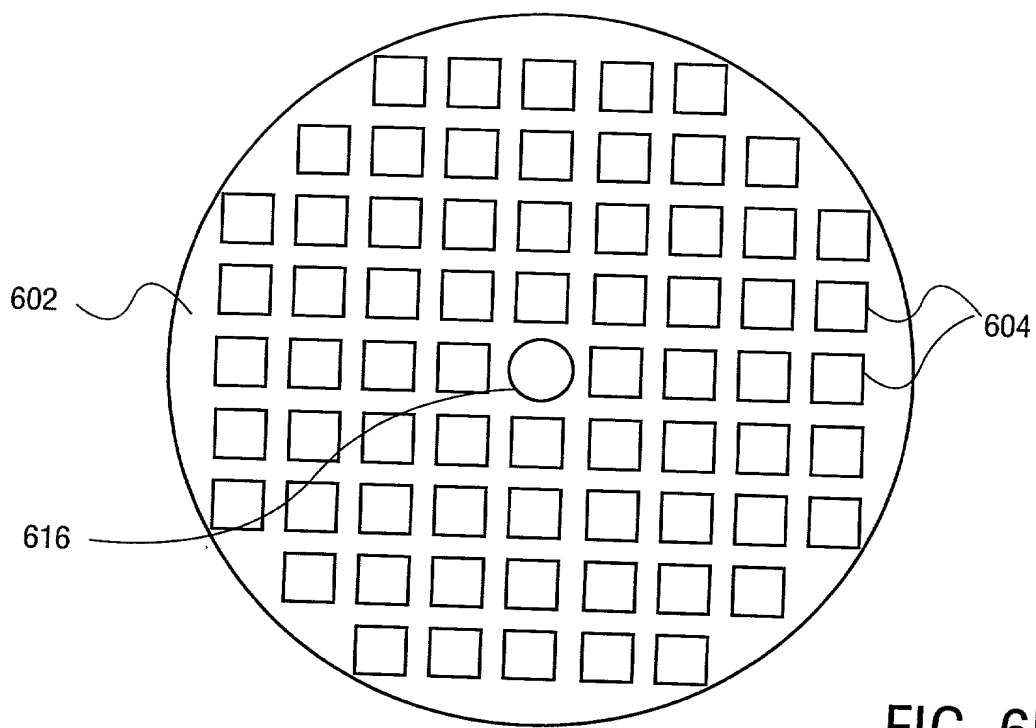


FIG. 6b

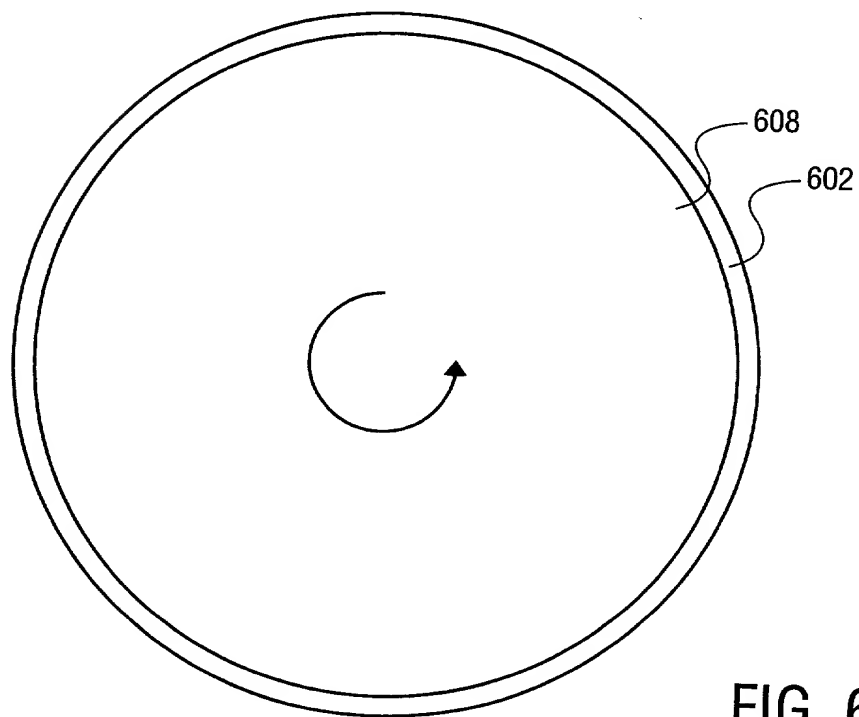


FIG. 6c

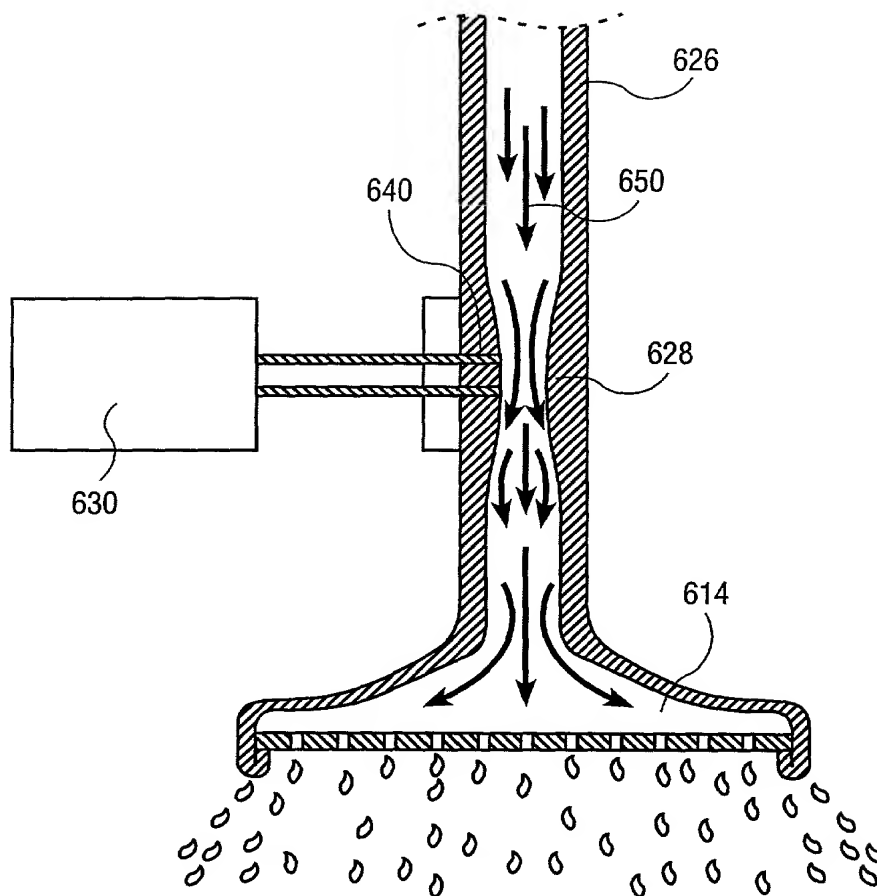


FIG. 6d

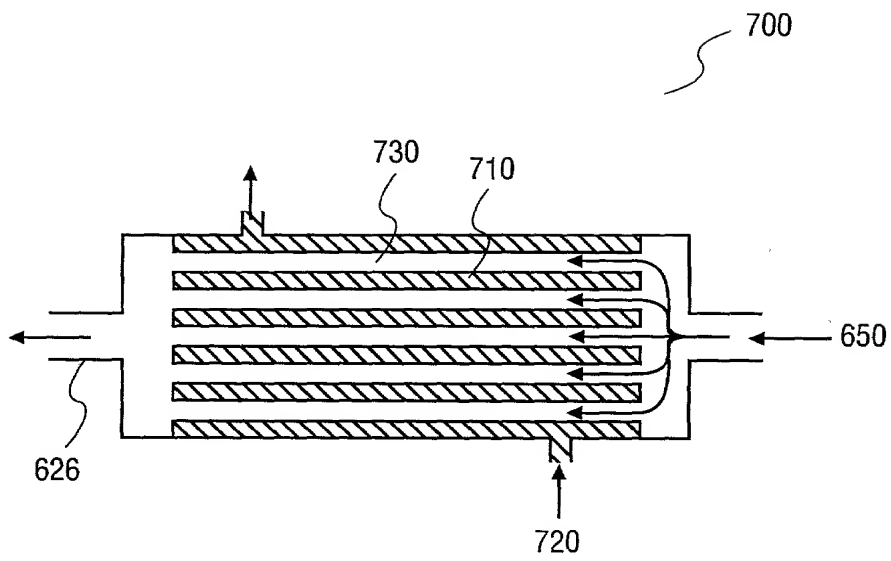


FIG. 7a

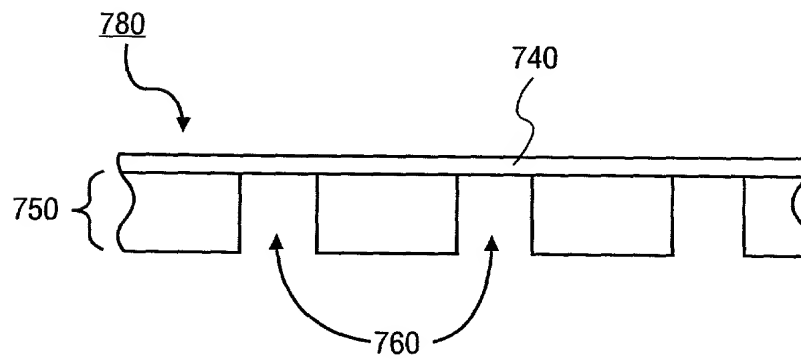


FIG. 7b

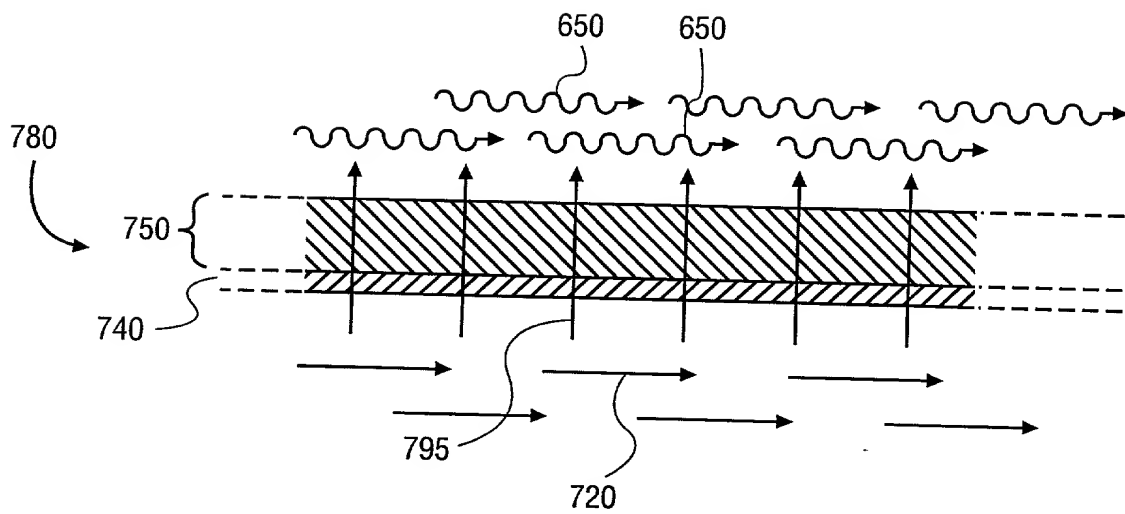


FIG. 7c

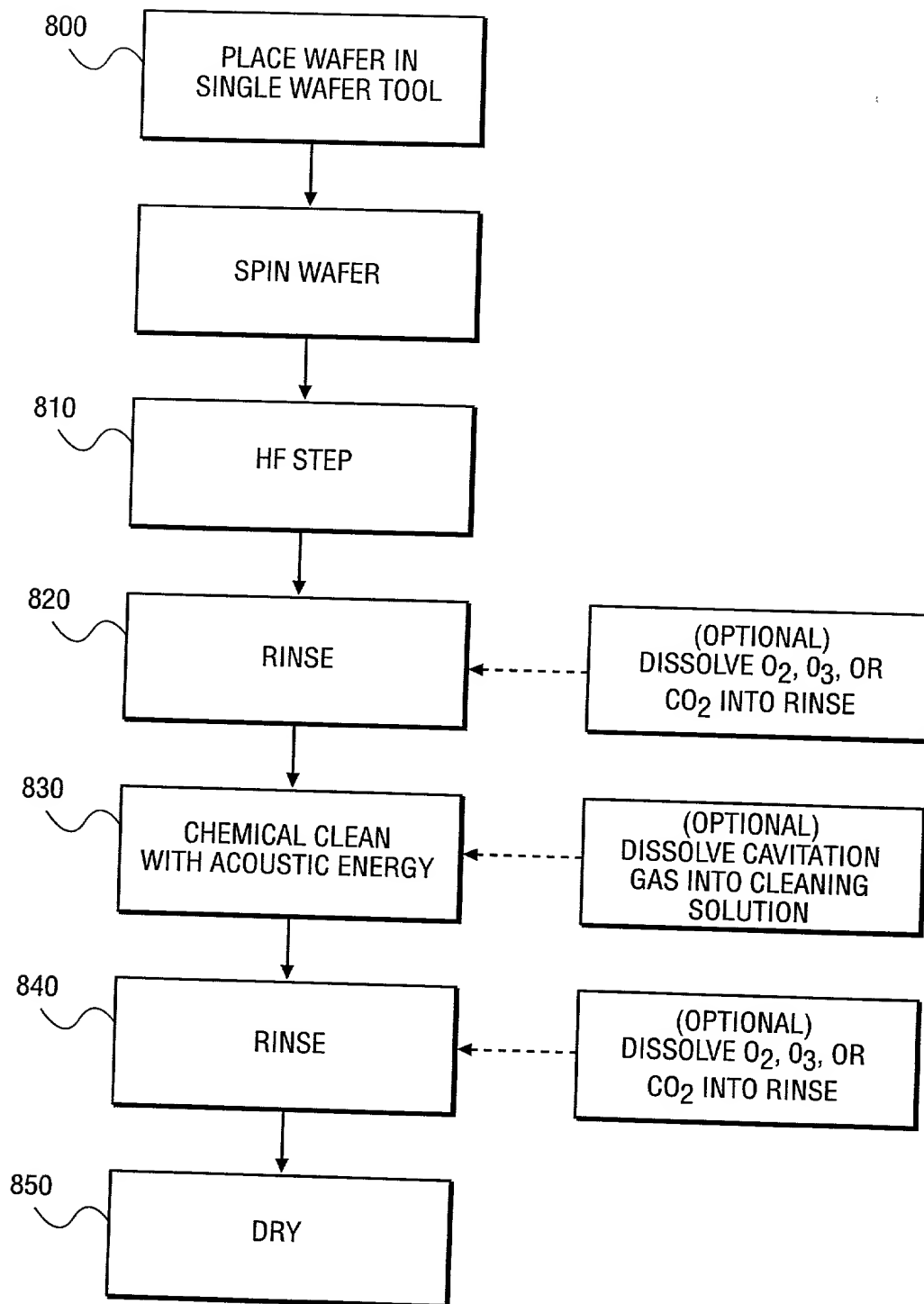


FIG. 8

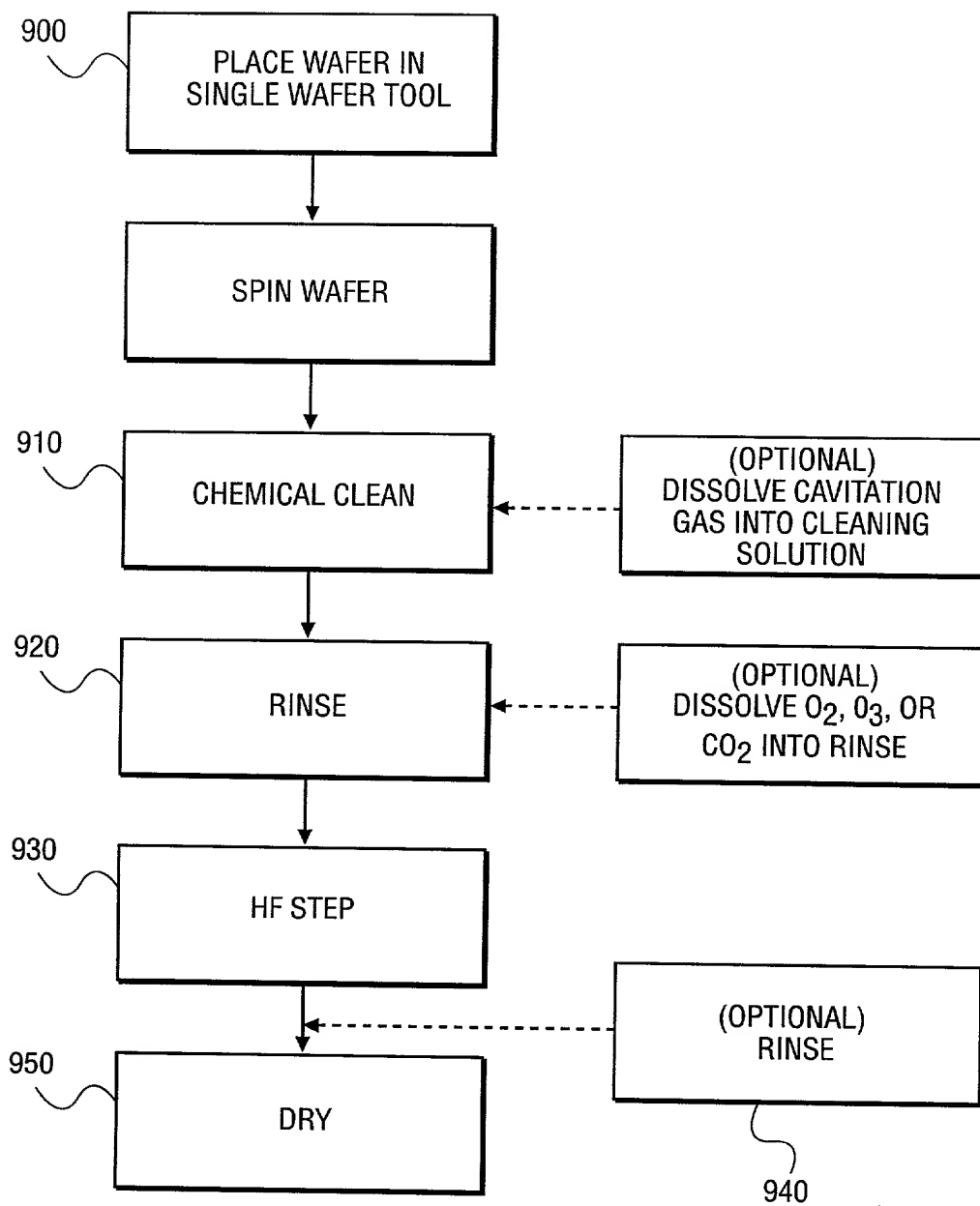


FIG. 9

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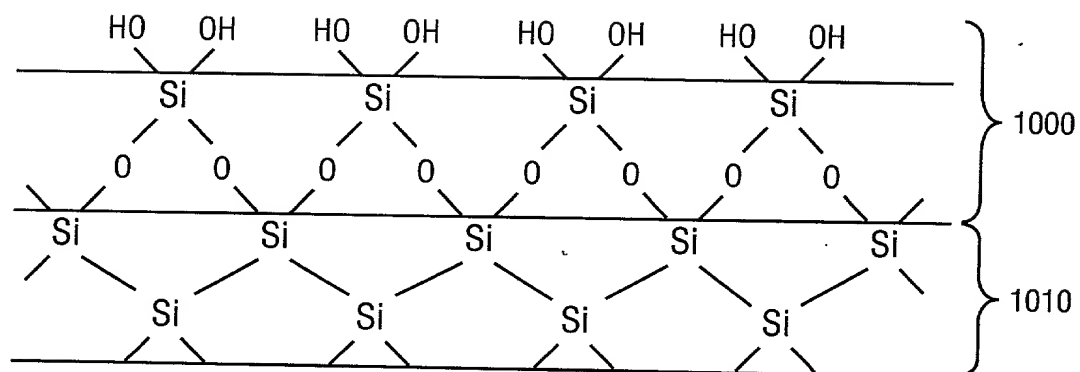
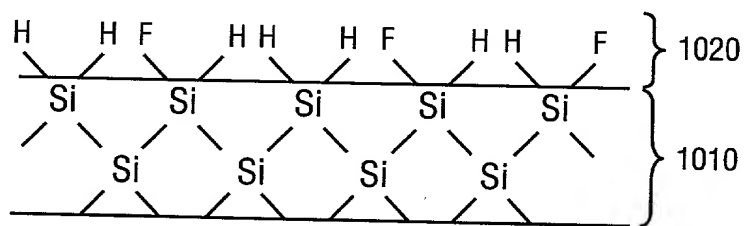


FIG. 10a



HYDROPHOLIC SURFACE

FIG. 10b

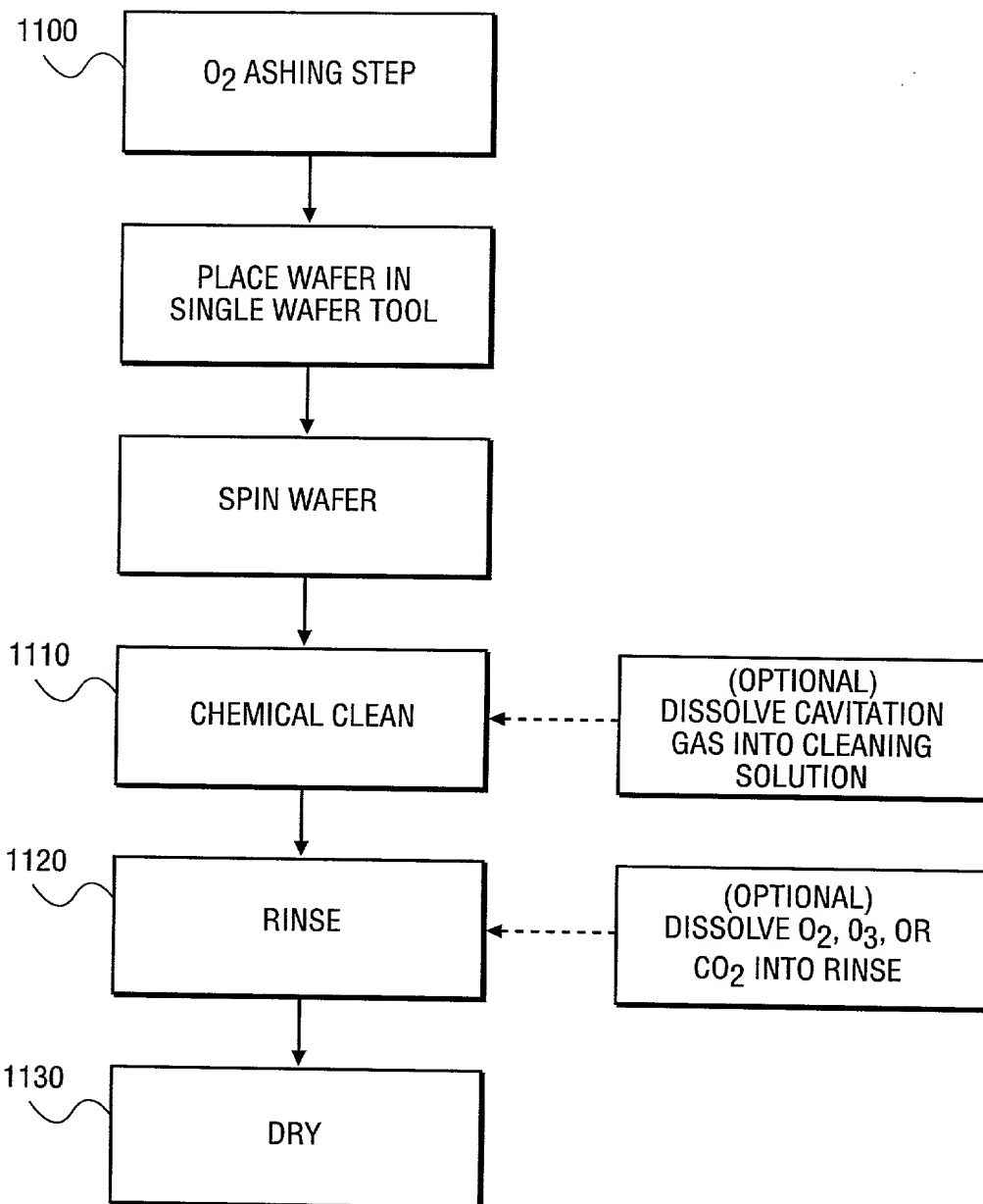


FIG. 11

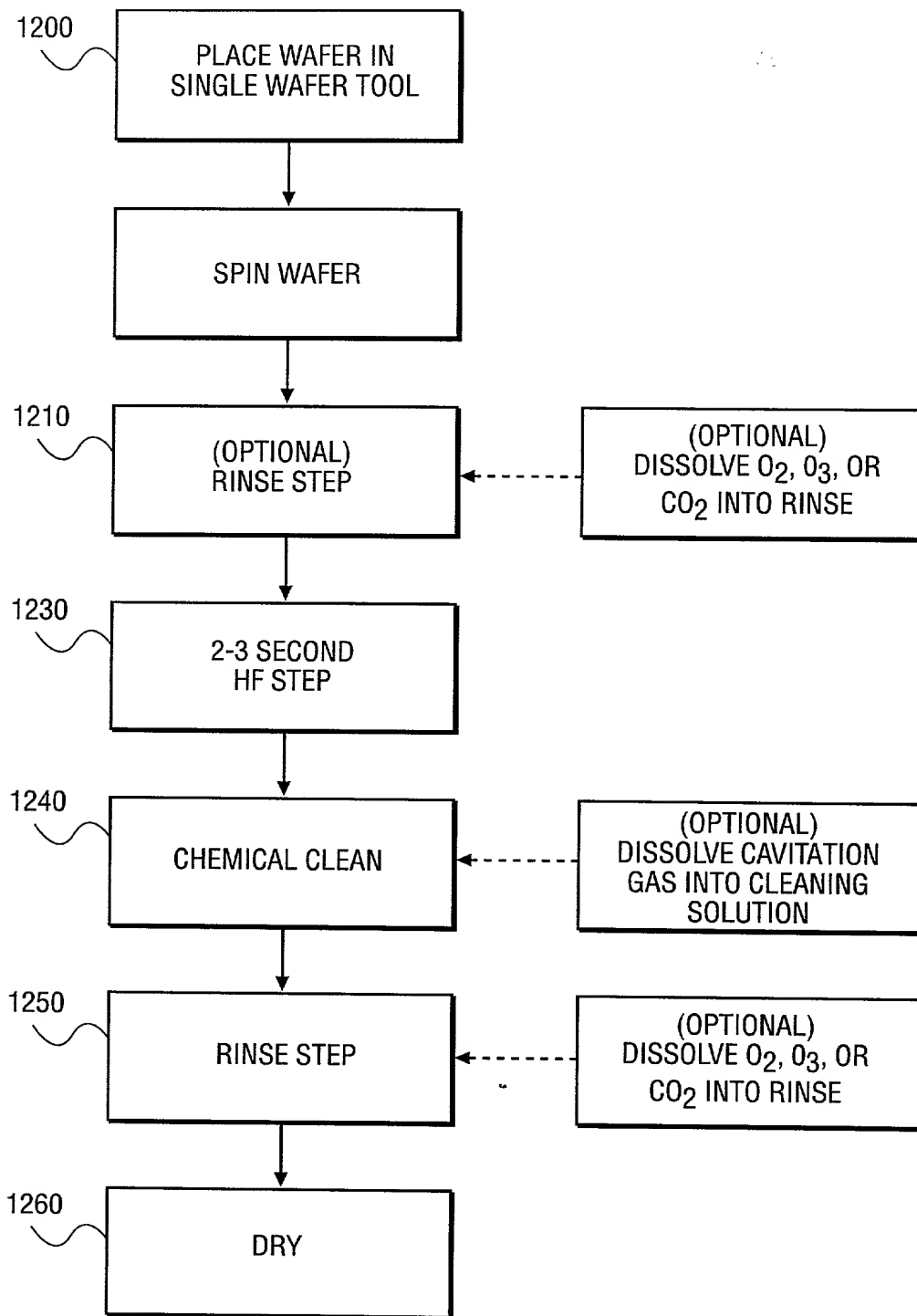


FIG. 12

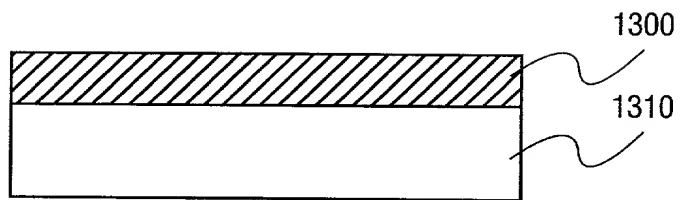


FIG. 13a

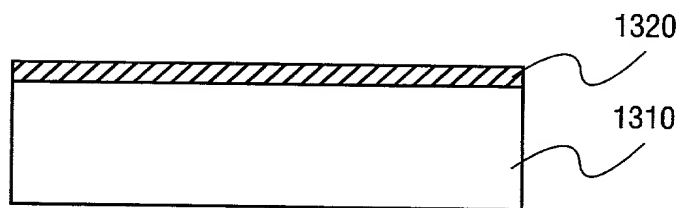


FIG. 13b